THERMAL IMPACT OF THERMAL INTERFACE MATERIALS AND HEAT SPREADER CO-PLANARITY OF THE ELECTRONIC PACKAGING

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THERMAL IMPACT OF THERMAL INTERFACE MATERIALS AND HEAT SPREADER CO-PLANARITY OF THE ELECTRONIC PACKAGING

by

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LIST OF SYMBOLS

A _{nominal}	Nominal area of heat transfer m ²		
A _{real}	Real area of heat transfer m ²		
h	Convection heat transfer coefficient W/m^2 . ^o C		
j*	Radiant emittance of a black body W/m ²		
k	Thermal conductivity of material W/m.K		
Р	Applied pressure Pa		
P _H	Heat dissipation of the device W		
\dot{Q}_{cond}	Heat flow by conduction W		
\dot{Q}_{conv}	Heat flow by convection W		
\dot{Q}_{rad}	Heat flow by radiation W		
R _{Board}	Thermal resistance of printed circuit board °C/W		
R _{Bump}	Thermal resistance of solder bump °C/W		
R _C	Area-normalized thermal contact resistance $K.m^2/W$		
R _{Die}	Thermal resistance of die °C/W		
R _{Die/TIM}	Contact resistance of die to TIM °C/W		
R _{Sub}	Thermal resistance of substrate °C/W		
R_{SB}	Thermal resistance of solder ball °C/W		
R _{TIM/HS}	Contact resistance of TIM to heat spreader °C/W		
R _{TIM}	Area-normalized thermal resistance K.m ² /W		
T _A	Ambient temperature °C		
T _B	Board temperature ^o C		
T _C	Case temperature ^o C		
T _J	Junction temperature of the device °C		
$\frac{\Delta T}{\Delta x}$	Temperature gradient in x direction K/m		

σ	Constant of proportionality W/m ² K ⁴	
σ_{C}	Surface roughness of two contact surface m	
8	Emissivity	
θ_{BA}	Thermal resistance board-to-ambient °C/W	
θ_{CA}	Thermal resistance case-to-ambient °C/W	
θ_{JA}	Thermal resistance junction-to-ambient °C/W	
θ_{JB}	Thermal resistance junction-to-board °C/W	
Θ_{JC}	Thermal resistance junction-to-case °C/W	

LIST OF ABBREVIATIONS

- BGA Ball Grid Array
- BLT Bond Line Thickness
- CFD Computational Fluid Dynamics
- CTE Coefficient of Thermal Expansion
- JEDEC Joint Electron Device Engineering Council
- PCB Printed Circuit Board
- POD Package Outline Drawing
- QFN Quad Flat No-leads
- TIM Thermal Interface Material
- TIM1 Thermal Interface Material 1
- TIM2 Thermal Interface Material 2

IMPAK TERMA BAGI BAHAN ANTARA MUKA TERMA DAN PENYEBAR HABA BAGI PAKEJ ELEKTRONIK

ABSTRAK

Tesis ini membentangkan impak terma yang disebabkan oleh sifat-sifat bahan antara muka terma dan kerataan penyebar haba ke atas pakej elektronik flip chip yang diintegrasikan bersama penyebar haba. Bahan antara muka terma mempengaruh kecekapan pemindahan haba dari silikon ke bungkusan pakej elektronik flip chip. Kerataan penyebar haba mengubah prestasi terma dalam pakej elektronik flip chip secara kerata, terutamanya rintangan pemindahan terma dari silikon ke bungkusan pakej elektronik. Kajian berangka menggunakan ANSYS Icepak telah dijalankan untuk menyiasat kesan terma yang disebabkan oleh sifat-sifat bahan antara muka terma dan kemerosotan terma yang disebabkan oleh penyebar haba yang mempunyai pesongan cekung atau cembung sebanyak 0.12 mm. Keputusan menunjukkan bahawa ketebalan dan kekonduksian terma bahan antara muka terma mempengaruh prestasi pemindahan haba dalam pakej elektronik flip chip. Keputusan juga menunjukkan bahawa pesongan cekung menyebabkan penambahbaikan sebanyak 44 peratus sementara pesongan cembung menyebabkan kemerosotan sebanyak 80 peratus ke atas rintangan terma dari silikon ke bungkusan pakej elektronik flip chip. Hasil dari penyelidikan mencadangkan panduan dan cadangan reka bentuk untuk pemilihan bersama pelaksanaan bahan antara muka terma. Kekonduksian terma yang lebih tinggi dan bahan antara muka terma yang lebih nipis harus dipilih untuk prestasi terma yang lebih baik untuk pakej elektronik flip chip. Penemuan ini juga mengesyorkan toleransi kerataan kurang daripada 0.07 mm untuk penyebar haba dalam pakej elektronik flip chip yang bersaiz 60 mm x 60 mm dengan pelesapan haba sebanyak 150 W.

THERMAL IMPACT OF THERMAL INTERFACE MATERIALS AND HEAT SPREADER CO-PLANARITY OF THE ELECTRONIC PACKAGING

ABSTRACT

This thesis presents the thermal impact of thermal interface material 1 (TIM1) and heat spreader co-planarity to the flip chip package with heat spreader. The TIM1 material influences the efficiency of heat transfer from silicon die to the heat spreader while the co-planarity of heat spreader affects the thermal performance of the flip chip package significantly, especially on the junction-to-case thermal resistance of the package. Numerical studies using ANSYS Icepak were conducted to investigate the thermal impact contributed by the TIM1 material properties and thermal degradation due to heat spreader co-planarity in either concave or convex with deflections up to 0.12 mm. The result indicated that the bond line thickness (BLT) and the thermal conductivity of the TIM1 material affected the thermal performance of the flip chip package. The result also showed that with concave deflection improved up to 44 % while convex deflection degraded up to 80 % of the junction-to-case thermal resistance of the flip chip package. The outcome of the study is to propose design guidelines and recommendations for TIM1 material selection and implementation. Higher thermal conductivity and lower the BLT of TIM1 material shall be selected for better thermal performance of the flip chip package. The findings also recommended the co-planarity tolerance for the heat spreader shall not be greater than 0.07 mm for a 60 mm x 60 mm flip chip package with a heat dissipation of 150 W.

CHAPTER 1

INTRODUCTION

1.1 Introduction

The heat dissipation of electronic packaging is a growing challenge over the years due to demanding high performance and highly integrated functionalities of the electronic packages ranging from the industry to consumer products. The chip heat dissipation trend in the industries, such as the desktop, server and automotive application are on rising trends in the past decade as presented by Bar-Cohen (2014). The heat dissipation trend of the automotive application as illustrated in Figure 1.1 shows the heat dissipation is reaching 300 W with the heat flux around 240 W/cm². These electronic packages are processing big data at high speed, significantly produce heat that needs to be dissipated into the environment. Therefore, thermal management of electronic packages becomes very crucial to ensure the functionality, better reliability and longer life span of the package.



Figure 1.1 Chip Heat Dissipation Trend (Bar-Cohen et al., 2014)

In most of the high heat dissipation electronic packaging, a heat spreader is integrated to the electronic package to allow direct heat transfer from the silicon die in either direction; through the bottom or the top of the packaging. Heat transfer through the bottom occurs in downward direction to dissipate heat via the printed circuit board such as Quad Flat No-leads (QFN) package. The heat transfer of the QFN package as defined by NXP is shown in Figure 1.2. The QFN package usually has lower pin counts and provides lesser electronic functionalities compared to Ball Grid Array (BGA) packages. The downward direction will not be discussed in the research.



Figure 1.2 Heat Transfer of the QFN package (NXP Application Note, 2018)

On the other hand, the heat transfer through the top and dissipates heat in upward direction through an external heat sink attached to the top of the packaging such as the flip chip package with integrated heat spreader is studied and discussed. A common example of the case study of the latter can be found is the microprocessor of computer, which a highly thermal conductivity heat spreader that is made of copper, placed at the top of the silicon die that helps to accelerate heat transfer from the silicon die to an external heat sink. The heat will eventually dissipate into the environment by a natural or forced air convection system. The heat transfer of the flip chip package with heat spreader and an external heat sink as presented by Galloway et al. (2011) as shown in Figure 1.3.



Figure 1.3 Heat Transfer of Flip Chip Package (Galloway et al., 2011)

The heat spreader is usually made by sheet metal forming and therefore, inherits manufacturing tolerances such as the co-planarity and surface finishing characteristics. When a heat spreader is required on a flip chip package, the thermal interface material or known as the TIM1 material in the industry is introduced to fill up the air gap between the silicon die and the heat spreader. The TIM1 material functions to ensure effective heat transfer between the silicon die and the heat spreader are the key determination factors that vary the thermal resistance between junction and the case of the package, which is known as junction-to-case thermal resistance, Θ_{JC} . The scope of this research is mainly to investigate the thermal impact of the TIM1 material and the co-planarity of heat spreader using using computational fluid dynamics (CFD) simulation approach.

1.2 Problem Statement

Packaging thermal characterization data that comply with JEDEC standard is pre-requisite for any new electronic package introduction into the market. These data are made available to end users and could be found in all the package datasheets. The characterization data include the junction-to-ambient thermal resistance or theta-JA (Θ_{JA}), the junction-to-board thermal resistance or theta-JB (Θ_{JB}) and the junction-tocase thermal resistance or theta-JC (Θ_{JC}). Θ_{JA} value is essential to the end user during the heat sink selection in the system design as presented by Lee (1995) and to determine whether a natural or forced air convection cooling design is needed. While Θ_{JB} and Θ_{JC} are very crucial to the design engineer especially when the product designer wants to predict the maximum junction temperature ($T_{JUNCTION}$ or T_J) of the electronic package in the system using CFD simulation. Most of the CFD simulation tools allow packaging modeling simplification by using two resistance model or also known as 2R model without the need to build a detail packaging model in the simulation as presented by Shidore et al. (2001) and (2007). The 2R model is defined in JESD 15-3 (2008) and the 2R refers to the Θ_{JB} and Θ_{JC} values provided in the package datasheet.

The thermal characterization data are generated from thermal simulation analyses based on detailed packaging models which are modelled by the package thermal engineer. Normally, thermal characterization analyses are carried out with the assumptions that all parts in the packaging are at nominal and perfect conditions. There is no co-planarity issue on all the parts and the TIM1 material fills up the air gap between the silicon die and the heat spreader perfectly without any void. However, in reality, the warpage can be easily found on the heat spreader and it becomes even more severe when the package size is bigger with heat spreader of larger surface area. The co-planarity of the heat spreader creates void in TIM1 material will eventually degrades the heat transfer from silicon die to the heat spreader. As a result, the junction-to-case thermal resistance increases significantly. Typically, for a flip chip package with a heat spreader, Θ_{JC} in the range of 0.05 to 0.10 °C/W as presented by Galloway et al. (2018). For a high power package, a small variation of Θ_{JC} value will cause a significant difference on T_J. For instance, a package with a heat dissipation of 300 W undergo a variation of 0.05 °C/W on Θ_{JC} will cause 15 °C difference at the junction temperature. Therefore, the accuracy of Θ_{JC} value is very important in order to prevent overestimation or underestimation of the maximum junction temperature of the package that will increase total product cost by introducing unnecessary cooling system. A comprehensive investigation needs to be carried out to further understand the relation and the impact of TIM1 material and coplanarity of the heat spreader to a high power flip chip package.

1.3 Research Objectives

The objectives of this research are as the following:

- a) To conduct steady state thermal simulation analysis to determine the behavior of TIM1 material to the thermal performance of the flip chip package.
- b) To come out with simulation model that able to mimic the void created by the heat spreader co-planarity and determine the impact to the thermal performance of the flip chip package using CFD simulation approach.
- c) To come out with design recommendations and guidelines for future package development based on the findings from simulation analysis.

1.4 Scopes

Thermal simulations that are carried out to investigate the thermal impact of the TIM1 material and co-planarity of the heat spreader include the simulation to characterize the junction-to-ambient thermal resistance, junction-to-board thermal resistance and the junction-to-case thermal resistance of the package. The junction-toambient thermal resistance simulations are in compliance with JEDEC, JESD51-2 and JESD51-2A and run at natural convection environment until steady state are reached. While the junction-to-board and junction-to-case thermal resistance simulations are compliance with JEDEC, JESD51-8 and JESD51-14 (Draft) respectively. These characterizations are simulated under pure conduction condition until steady state are reached.

There are total of four different TIM1 materials with different thermal conductivities and contact resistances are selected for the thermal performance investigation. The thermal performance of TIM1 materials are compared at the severe bond line thickness (BLT) of 0.08 mm, 0.12 mm and 0.16 mm with the assumptions that the heat spreaders are perfectly flat without co-planarity issue.

Whereas, the heat spreader with concave and convex profiles with deflection of 0.02 mm, 0.04 mm, 0.06 mm, 0.08 mm, 0.10 mm and 0.12 mm are investigated under heat spreader co-planarity study. The TIM1 material is fixed to Shin-Etsu X23-7772-4 with thermal conductivity, k_{TIM1} is 3.8 W/m.K and BLT is 0.12 mm in all the heat spreader co-planarity investigations.

1.5 Outline of Thesis

There are a total of five chapters in this thesis. Chapter 1 discusses about the current trend of the electronic packaging and provided some backgrounds on the issues faced by electronic package engineer in the industry. Also stated are the problem statement, objectives, scope of the research and the outline of this thesis.

Chapter 2 provides a comprehensive literature review to go through the detailed construction and thermal management of a flip chip package. Several key elements that influenced the thermal characteristic of the flip chip package are addressed in this section.

Subsequently, Chapter 3 explains the simulation models used throughout the research. The simulation modelling, meshing and boundary conditions are discussed in detail. Last but not least, the evidence of correlation between simulation results and the actual experimental measurement results are presented and subsequently these simulation models with similar settings are used as the baselines for the future simulations.

Chapter 4 presents the simulation results throughout this research. The simulations are divided into two groups, the variation of TIM1 material and the coplanarity of the heat spreader. The co-planarity of heat spreader includes the concave deflection, convex deflection with paste type and film type TIM1 material configurations. Discussion of the findings, design guidelines and recommendations are presented at the end of the chapter. The final chapter, Chapter 5 provides an overall conclusion from the investigations, the limitations of the research and recommendations for the future research.

CHAPTER 2

LITERATURE REVIEW

2.1 Introduction

This chapter presents the literature reviews based on JEDEC standards, technical papers, patents, journals and final year projects from previous students. The reviews of the flip chip package technology included the detailed constructions of the flip chip package, the heat spreader technologies and the TIM1 materials in the flip chip package. The thermal management of the flip chip package, mainly the thermal resistances and heat transfer mechanism of a flip chip package are also being reviewed in this chapter.

2.2 Flip Chip Package

2.2.1 Flip Chip Package Construction

Lau (1996) defined a flip chip as a chip that is attached to the pads of a substrate or another chip with various interconnect materials and methods, as long as the chip surface was facing the substrate as show in Figure 2.1.



Figure 2.1 Definition of Flip Chip Package (Lau, 1996)

Lau (1996) described that the chip or the silicon die is bumped before flipped onto a substrate. The bumps are distributed across the entire chip and not only located on the die edge and therefore intellectual property (IP) blocks could be placed all over the surface of the die. This allows designer to place more IP blocks per die, which reduces the chip size and optimise signal integrity. The substrate provides connectivity from silicon die to the external print circuit board via bumps and solders balls. It also absorbs heat from silicon die via bumps and dissipates heat to the print circuit board via solder balls. The underfill material is used to fill the air gap between the bumps, silicon die and the substrate, providing better adhesion of the silicon die to the substrate. At the same time, underfill also helps in heat transfer between silicon die and the substrate as the underfill thermal conductivity is usually higher than air as listed in Table 2.1. The cross-sectional view of the flip chip package is shown in Figure 2.2.

Material	Thermal Conductivity (W/m.K)
Copper	387.6
Aluminum	200
Silicon	120
Mold compound	0.9
Solder	57.2
Substrate Dielectric	0.25
Underfill	0.5
Air	0.025

Table 2.1 Package Material Thermal Conductivity List (IDT Application Note, 2014)



Figure 2.2 Cross-sectional View of Flip Chip Package (Lau, 2016)

For a high power flip chip package, a heat spreader is placed on top of the silicon die to provide more superior heat transfer from silicon die to the external environment. And the heat spreader is usually made of high thermal conductivity material such as copper with k = 387.6 W/m.K. A thermal interface material (TIM) would be used as the gap filler to fill up the air gap between silicon die and the heat spreader and therefore provide more effective heat conduction between silicon die and the heat spreader. The cross-sectional view of a flip chip package with integrated heat spreader as presented by Gan et al. (2009) is shown in Figure 2.3.



Figure 2.3 Cross-sectional View of Flip Chip Package with Heat Spreader (Gan et al., 2009)

2.2.2 Reviews on Heat Spreader

The evolution of flip chip package was described by Ranade (2005) in the article '*Packaging Technology Ready for Change*'. The flip chip package has evolved from the drivers such as performance, cost, I/O density and thermal impedance have pushed the package designers to develop suitable solutions instead of 'one size fits all' solutions in the traditional flip chip package design. The thermal impedance and cost that drove the subcomponent costs reduction on the flip chip package has pushed for the evolution of heat spreader design in flip chips.

The outlines of the evolution of heat spreader design in flip chip packages are shown in Figure 2.4. A single piece of stamped heat spreader that pushed the Niplated stiffener and heat spreader combination to the end is driven by the process simplification and cost. Future improvements include a strip format overmolded substrates with drop-in heat spreaders or simple bare die with direct attachment of heat sinks as presented by Ranade (2005).



Figure 2.4 Evolutions of Heat Spreader in Flip Chip Package (Ranade, 2005)

2.2.3 Reviews on Thermal Interface Material

Gowda et al. (2005) explained the thermal interface material between silicon die and heat spreader is typically designated as TIM1 and the thermal interface material between heat spreader and an external heat sink is designated as TIM2 as shown in Figure 2.5. The thermal interface material solutions exist in several forms, such as adhesive, greases, gels, phase change material and pads. Each of these TIM solutions have certain advantages and disadvantages. Most of the thermal interface materials consist of polymer matrix, such as an epoxy or silicone resin and thermally conductive filler such as boron nitride, alumina, aluminium, zinc oxide and silver.



Figure 2.5 Definition of TIM1 and TIM2 Materials (Gowda et al., 2005)

Gowda et al. (2005) further described several performance metrics that were used to describe the thermal performance of the thermal interface material namely, the thermal conductivity, apparent or in-situ conductivity, thermal resistance and thermal impedance. Thermal conductivity is the ability to conduct heat across the material. Apparent or in-situ conductivity takes into account of the contact resistances between thermal interface material and the interface components. In fact, the apparent or in-situ conductivity more precisely represents the actual performance of the thermal interface material. Thermal resistance and impedance represent the resistances of heat flow across the interface material. Figure 2.6 illustrates the cross-sectional view of thermal interface material.



Figure 2.6 Cross-sectional View of Thermal Interface Material (Gowda et al., 2005)

In another publication, Gowda et al. (2004) also reported the effect of void and their characteristics to the thermal performance of the TIM material adhesive layers. Voids were quantified and experimented to check for the in-situ thermal conductivity for several TIM materials, as shown in Figure 2.7. The report showed that the increasing of void sizes in the TIM materials decrease the in-situ thermal conductivity of the TIM materials that applicable to both of the TIM1 and TIM2 materials. However, the voids are investigated independently and the relation of void created due the co-planarity of heat spreader is not addressed in the study.



Figure 2.7 In-situ Thermal Conductivity vs Percentage Voiding (Gowda et al., 2004)

Mahajan (2004) described after inserting a thermal interface material to solid surfaces, the effective thermal resistance, R_{TIM} , at the interface will have two components. The bulk resistance, R_{bulk} , of the thermal interface material arising from its finite thermal conductivity and the contact resistance, R_C between the thermal interface material and the adjoining solids, as shown in Figure 2.8. R_{TIM} can be calculated from Equation 1, this applicable to both of the TIM1 and TIM2 materials.



Figure 2.8 Schematic of Various Resistance Components of R_{TIM} (Prasher, 2006)

$$R_{TIM} = \frac{BLT}{k_{TIM}} + R_{C1} + R_{C2}$$
(1)

Where $R_{TIM} =$ area-normalized thermal resistance of TIM $(K.m^2\!/W)$

BLT = bond line thickness of TIM (m)

 k_{TIM} = thermal conductivity of TIM (W/m.K)

 R_{C1} & R_{C2} = area-normalized thermal contact resistances (K.m²/W)

In order to optimise the heat transfer by conduction, R_{TIM} should be minimized. This could be accomplished by reducing the BLT, increase thermal conductivity and reduce the contact resistances R_{C1} and R_{C2} .

Prasher et al. (2003) addressed the bond line thickness is a function of various parameters such as the application pressure and the particle volume fraction. The bond line thickness could be calculated from Equation 2. The higher the application pressure onto the thermal interface material would reduce the bond line thickness and thus reduce the thermal resistance of thermal interface material.

$$BLT = 1.31 x 10^{-4} \left(\frac{\tau_y}{P}\right)^{0.166}$$
(2)

Where BLT = bond line thickness of TIM (m)

 $\boldsymbol{\tau}_{y}$ = yield stress of TIM (MPa)

P = applied pressure (Pa)

Prasher et al. (2001) stated that the total of contact resistances of the thermal interface material could be determined by Equation 3.

$$\boldsymbol{R_{C1+2}} = \left(\frac{\sigma_1 + \sigma_2}{2k_{TIM}}\right) \left(\frac{A_{nominal}}{A_{real}}\right) \tag{3}$$

Where R_{C1+2} = total contact resistances (K.m²/W)

 σ_1 & σ_2 = surface roughness of two contact surfaces (m)

 k_{TIM} = thermal conductivity of TIM (W/m.K)

 $A_{nominal} = nominal area of heat transfer (m²)$

 $A_{real} = real area of heat transfer (m²)$

 A_{real} is always smaller than the nominal contributed by the air trapped in the wetting area. The contact resistance could be minimized by decreasing the surface

roughness, increase the thermal conductivity of interface material and minimise the air trapped in the interface area.

The thermal resistance versus bond line thickness chart (TR vs BLT) could be found in the thermal interface material datasheet. For instance, the TR vs BLT chart for X-23-7772-4 TIM1 material from Shin-Etsu is shown in Figure 2.9. The thermal conductivity shown in the chart represents the apparent thermal conductivity which is always lower than the bulk thermal conductivity, 3.8 W/m.K as given in the datasheet. The thermal contact resistance given in the TR vs BLT graph could be referred to the total contact resistance across the interface material which consisted of the contact resistances on the top and the bottom of the interface material as shown in Figure 2.6 and Figure 2.8. This explains why the apparent or in situ thermal conductivity is essential for package development during thermal interface material selection.



Figure 2.9 TR vs BLT Data for X-23-7772-4 (Shin-Etsu Datasheet)

2.3 Thermal Management of Flip Chip Package

2.3.1 Thermal Resistance

The application note of IDT (2014) explained that thermal resistance is the measure of a material's capability to resist the heat flow which could be in the form of conduction, convection or radiation. Thermal resistance is commonly used to evaluate and compare the thermal performance of the electronic package based on JEDEC standard. The relationship between thermal resistance, heat flow and the temperature differences is shown in Equation 4.

$$\boldsymbol{\Theta} = \frac{\Delta T}{P} \tag{4}$$

Where Θ = thermal resistance (°C/W)

 ΔT = temperature differences across the material (°C)

P = heat flow or the power applied to the material (W)

IDT (2014) further described that junction-to-ambient thermal resistance (Θ_{JA}) measured the ability of a package to dissipate heat from the silicon die to the ambient environment through convection and radiation. The junction-to-ambient thermal resistance (Θ_{JA}) under this condition could be determined from Equation 5 as defined in JEDEC standard, JESD 51-2 and JESD 51-2A.

$$\boldsymbol{\Theta}_{JA} = \frac{T_J - T_A}{P_H} \tag{5}$$

Where Θ_{JA} = thermal resistance from junction-to-ambient (°C/W)

 T_J = junction temperature of the device at steady state (°C)

 T_A = ambient temperature at steady state (°C)

 P_H = heat dissipation of the device (W)

The heat transfer from silicon die to top surface of heat spreader is measured by the junction-to-case thermal resistance (Θ_{JC}) and the heat transfer from silicon die to the printed circuit board is measured with junction-to-board thermal resistance (Θ_{JB}) through conduction. There are heat transfers from the heat spreader and board to the ambient as well, and those could be measured by the board-to-ambient (Θ_{BA}) and case-to-ambient (Θ_{CA}) thermal resistance respectively. Figure 2.10 shows the heat transfer and thermal resistances schematic for a flip chip package with heat spreader. And the junction-to-ambient (Θ_{JA}) thermal resistances diagram of a flip chip package could be simplified as shown in Figure 2.11.

• Ambient Temperature, T_A



Figure 2.10 Heat Transfer and Thermal Resistance Schematic for a Flip Chip Package (IDT Application Note, 2014)



Figure 2.11 Junction-to-Ambient Thermal Resistance Diagram of a Flip Chip Package (IDT Application Note, 2014)

Junction-to-board thermal resistance (Θ_{JB}) is used to measure the conduction of heat from silicon die to the print circuit board. The junction-to-board thermal resistance (Θ_{JB}) under this condition could be determined from Equation 6 according to JEDEC standard, JESD 51-8.

$$\boldsymbol{\Theta}_{JB} = \frac{T_J - T_B}{P_H} \tag{6}$$

Where Θ_{JB} = thermal resistance from junction-to-board (°C/W)

 T_J = junction temperature of the device at steady state (°C)

 T_B = board temperature at steady state (°C)

 P_H = heat dissipation of the device (W)

Heat conduction from the silicon die to the printed circuit board is shown in Figure 2.12. Each of the silicon die, bumps, underfill, substrate, solderballs and board

has its own thermal resistance. The junction-to-board thermal resistance of the package is the summation of all these thermal resistances and could be calculated from Equation 7.



Figure 2.12 Secondary Heat Path Diagram of a Flip Chip Package (Shin-Etsu Datasheet)

$$\boldsymbol{\Theta}_{JB} = \boldsymbol{R}_{JB} = \boldsymbol{R}_{Die} + \boldsymbol{R}_{Bump} + \boldsymbol{R}_{Sub} + \boldsymbol{R}_{SB} + \boldsymbol{R}_{Board}$$
(7)

Junction-to-case thermal resistance (Θ_{JC}) measured the ability of a package to conduct heat from silicon die to case. The junction-to-case thermal resistance (Θ_{JC}) under this condition could be determined from Equation 8:

$$\boldsymbol{\Theta}_{JC} = \frac{T_J - T_C}{P_H} \tag{8}$$

Where Θ_{JC} = thermal resistance from junction-to-case (°C/W)

 T_J = junction temperature of the device at steady state (°C)

 T_C = case temperature at steady state (°C)

 P_H = heat dissipation of the device (W)

Figure 2.13 shows the detailed heat path from the active side of die to the top of lid, heat spreader. Each of the components such as silicon die, TIM1 material and

heat spreader has its own thermal resistance. There are two contact resistances along the heat path, one at the top and another at the bottom of the TIM1 material. The existence of these two contact resistances are contributed by the bond line thickness between TIM1 material with the silicon die and the heat spreader. The contact resistance is contributed by the surface roughness of the parts itself. The summation of these thermal resistances develops the junction-to-case thermal resistance of the package and could be summarized and calculated from Equation 9.



Figure 2.13 Primary Heat Path Diagram of a Flip Chip Package (Shin-Etsu Datasheet)

$$\boldsymbol{\Theta}_{JC} = \boldsymbol{R}_{JC} = \boldsymbol{R}_{Die} + \boldsymbol{R}_{Die/TIM} + \boldsymbol{R}_{TIM} + \boldsymbol{R}_{TIM/HS} + \boldsymbol{R}_{HS}$$
(9)

 $\langle \mathbf{n} \rangle$

2.3.2 Heat Transfer Mechanisms

According to heat transfer textbook by Çengel (2004), there are three modes of heat transfer occurred in a system, for instance the heat dissipation from a semiconductor packaging to the ambient. Heat can be transferred by conduction, convection and radiation.

Conduction is the measured of heat transfer between two material that are in direct contact. Fourier's law of heat conduction states that the time rate of heat transfer though a material is proportional to the negative of temperature gradient and cross sectional surface area. Fourier's equation of heat conduction is shown in Equation 10.

$$\dot{Q}_{cond} = -kA \frac{\Delta T}{\Delta x} \tag{10}$$

Where \dot{Q}_{cond} = heat transfer by conduction (W)

k = thermal conductivity of material (W/m.K)

A = cross-sectional surface area (m²)

 $\frac{\Delta T}{\Delta x}$ = temperature gradient in x direction (K/m)



Figure 2.14 Δx Distances in Flip Chip Package (IDT Application Note, 2014)

Equation 10 above could be rearranged as Equation 11.

$$\frac{\Delta x}{k \, x \, A} = \frac{\Delta T}{\dot{Q}_{cond}} = \Theta_{JC}, \, \Theta_{JB} \tag{11}$$

Equation 11 shows that the junction-to-board & junction-to-case thermal resistances are contributed by few factors. The higher thermal conductivity of material and the lower heat transfer distance from the junction will result a lower thermal resistance in a package. Thermal conductivity of the materials that are commonly used in the semiconductor packages are listed in Table 2.1. Table 2.1 shows that air has the lowest thermal conductivity. Therefore, air gap should be minimized in any contact surface because the air gap will significantly increase thermal resistance.